





L Number	Hits	Search Text	DB	Time stamp
1	1	("5793090").PN.	USPAT; US-PGPUB	2004/02/06 19:47
2	1	("6391731").PN.	USPAT; US-PGPUB	2004/02/06 19:46
3	1	("6548361").PN.	USPAT; US-PGPUB	2004/02/06 19:47
4	1	("5529951").PN.	USPAT; US-PGPUB	2004/02/06 19:47
5	4	((("5793090").PN.) or (("6391731").PN.) or (("6548361").PN.) or ("5529951").PN.)	USPAT; US-PGPUB	2004/02/06 20:00
6	1	("20020098689").PN.	USPAT; US-PGPUB	2004/02/06 20:00
7	70989	Ge or germanium	USPAT; US-PGPUB	2004/02/06 20:00
8	1	((("20020098689").PN.) and (Ge or germanium))	USPAT; US-PGPUB	2004/02/06 20:19
9	11918	LPCVD	USPAT; US-PGPUB	2004/02/06 20:21
10	1	("6548361").PN.	USPAT; US-PGPUB	2004/02/06 20:20
11	0	LPCVD and ("6548361").PN.)	USPAT; US-PGPUB	2004/02/06 20:20
12	1	((("20020098689").PN.) and LPCVD	USPAT; US-PGPUB	2004/02/06 20:20
13	14054	LPCVD or "low pressure chemical vapor deposition"	USPAT; US-PGPUB	2004/02/06 20:21
14	0	((("6548361").PN.) and (LPCVD or "low pressure chemical vapor deposition"))	USPAT; US-PGPUB	2004/02/06 20:21
15	1	((("20020098689").PN.) and (LPCVD or "low pressure chemical vapor deposition"))	USPAT; US-PGPUB	2004/02/06 20:37
16	435522	oxygen or silane	USPAT; US-PGPUB	2004/02/06 20:37
17	0	((("20020098689").PN.) and (oxygen or silane))	USPAT; US-PGPUB	2004/02/06 20:37
18	915433	O	USPAT; US-PGPUB	2004/02/06 20:38
19	1	((("20020098689").PN.) and O	USPAT; US-PGPUB	2004/02/06 20:43
20	1	((("6391731").PN.) and (LPCVD or "low pressure chemical vapor deposition"))	USPAT; US-PGPUB	2004/02/06 20:45
21	0	((("5793090").PN.) and (LPCVD or "low pressure chemical vapor deposition"))	USPAT; US-PGPUB	2004/02/06 20:46
22	2	((("6656749") or ("6426278"))).PN.	USPAT; US-PGPUB	2004/02/06 20:46

23	1	(LPCVD or "low pressure chemical vapor deposition") and (((("6656749") or ("6426278")).PN.)	USPAT; US-PGPUB	2004/02/06 20:48
24	1505	(LPCVD or "low pressure chemical vapor deposition") with (oxygen or silane)	USPAT; US-PGPUB	2004/02/06 20:52
25	96331	"CVD" or "chemical vapor deposition"	USPAT; US-PGPUB	2004/02/06 20:53
26	820	((LPCVD or "low pressure chemical vapor deposition") with (oxygen or silane)) with ("CVD" or "chemical vapor deposition")	USPAT; US-PGPUB	2004/02/06 20:53
27	74345	438/\$7.ccls.	USPAT; US-PGPUB	2004/02/06 20:53
28	613	((LPCVD or "low pressure chemical vapor deposition") with (oxygen or silane)) with ("CVD" or "chemical vapor deposition")) and 438/\$7.ccls.	USPAT; US-PGPUB	2004/02/06 21:18
29	4609	((438/517) or (438/522) or (438/530) or (438/660) or (438/663) or (438/680) or (438/685) or (438/761) or (438/763) or (438/785) or (438/787) or (438/791) or (438/923) or (438/933)).CCLS.	USPAT; US-PGPUB	2004/02/06 21:20
30	763	(Ge or germanium) and (((438/517) or (438/522) or (438/530) or (438/660) or (438/663) or (438/680) or (438/685) or (438/761) or (438/763) or (438/785) or (438/787) or (438/791) or (438/923) or (438/933)).CCLS.)	USPAT; US-PGPUB	2004/02/06 21:20